

FIG. 2

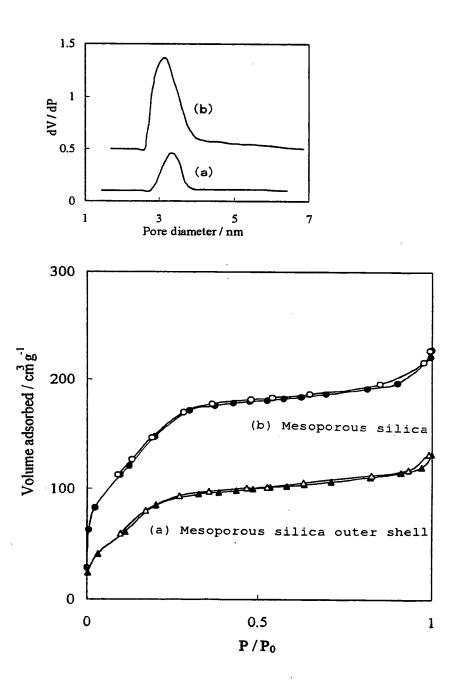


FIG. 3

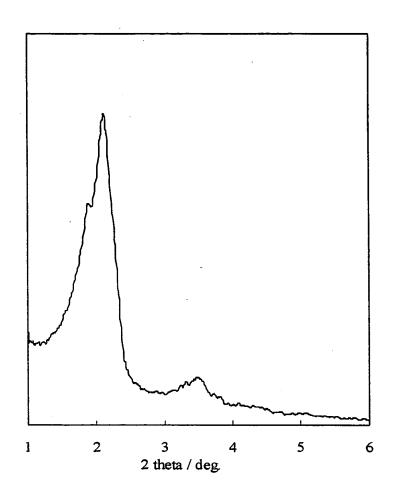


FIG. 4

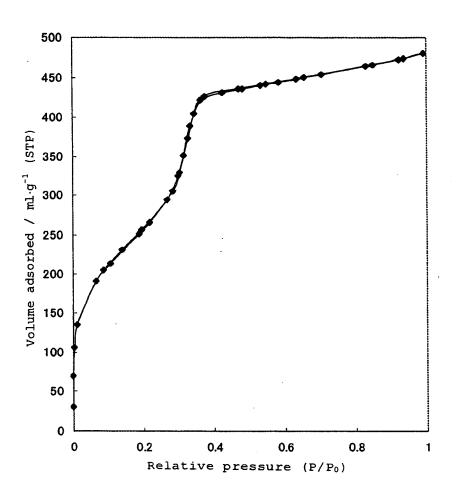


FIG. 5

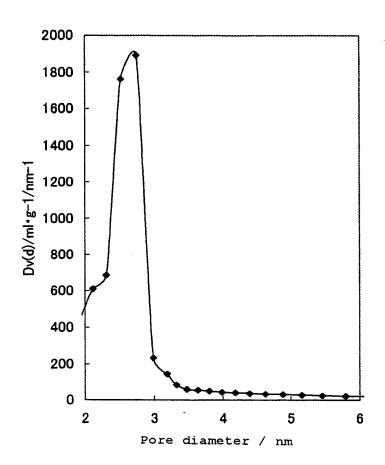


FIG. 6

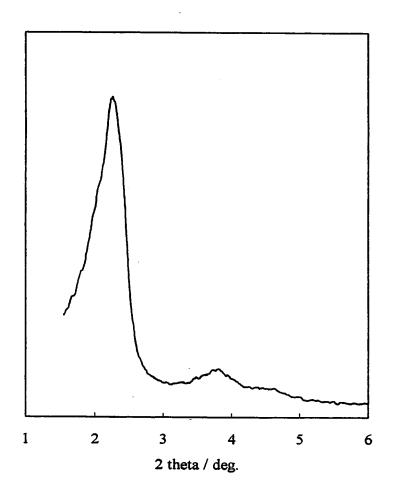


FIG. 7

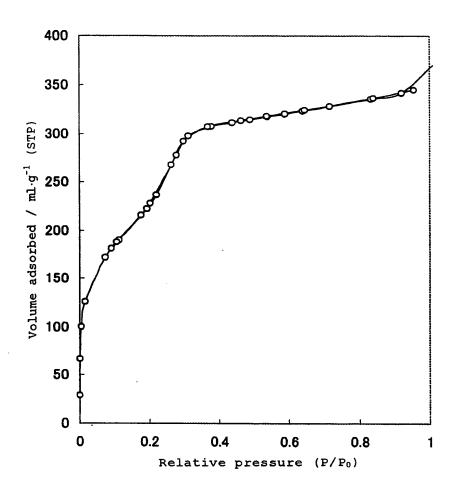


FIG. 8

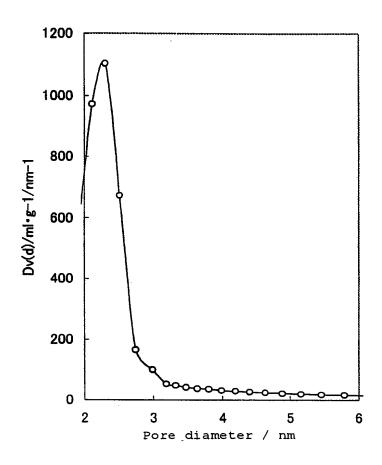


FIG. 9

	Neutralization	Double decomposition
Surfactant	~~~~~AH	~~~~~~A. W.
CSDA	H ₂ N—Si—OCH ₃ OCH ₃ OCH ₃ OCH ₃	H ₃ C + OCH ₃ H ₃ C Cl Si OCH ₃ OCH ₃ (TMAPS)
Interaction	Si WAN A H ₃ N Si A H ₃ N Si Si	H ₁ C + OSi H ₂ C + OSi H ₃ C + OSi H ₃ C + OSi H ₃ C + OSi Si
	$C_{n}H_{2n+1}, C_{n}H_{2n+1}C-NH-CH-C_{n}H_{2n+1}C-NH-CH$ R_{1} AH	
	A: COO, OSO ₃ , SO ₃ , OPO ₃ ; M ⁺ : Na ⁺ , K ⁺ , NH ₃ ⁺ etc.; R ₁ ; H, CH ₃ ; n = 8 - 18;	

FIG. 10

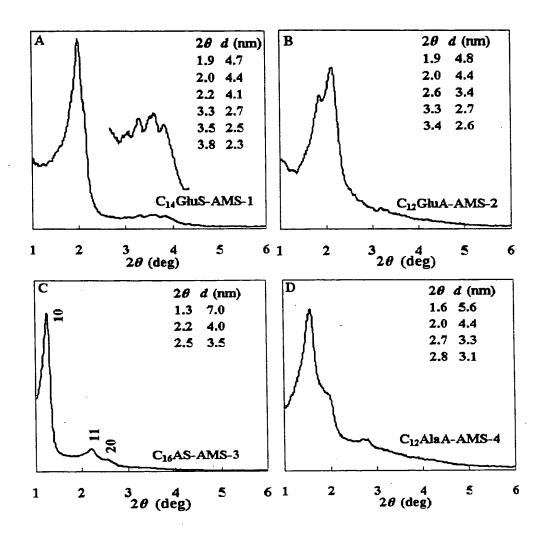


FIG. 11

Supporting on line materials:

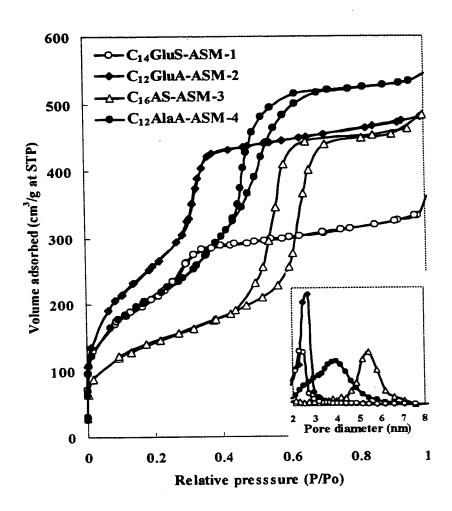


FIG. 12

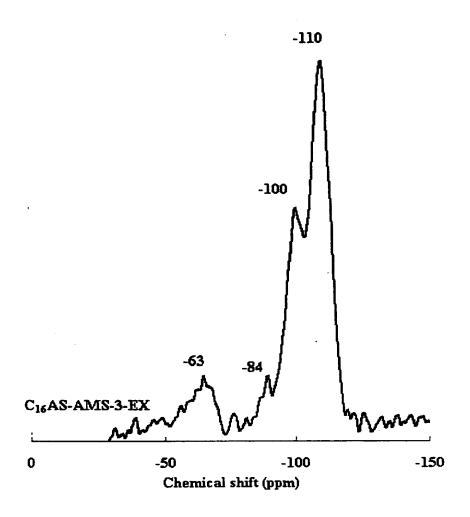


FIG. 13